Master: Agar patch device (Isa 3)

Clean :

* ddH2O
* Acetone
* Sonication
* Dehydration ( ***15*** *min* @ **120**°C )

Spin :

* ***HTexture*** = about ***120 μm***
* Photoresistor: negative **Su-3025**; was old (2011) and almost finished

We cannot build up 120 μm in one spin, thus we will do two consecutives ones, with soft baking in between to harden a bit first layer and avoid too have it modified by second spin.

|  |  |  |  |
| --- | --- | --- | --- |
| ***+60 μm*** | *Speed* | *ramp* | *Time* |
| 0° | 500 rpm | 1 | ***10*** *s* |
| 1° | 1000 rpm | 8 | ***30*** *s* |

Soft Bake 1 : t = ***15*** *min*

|  |  |  |  |
| --- | --- | --- | --- |
| ***+60 μm*** | *Speed* | *ramp* | *Time* |
| 0° | 500 rpm | 1 | ***10*** *s* |
| 1° | 1000 rpm | 8 | ***30*** *s* |

Soft Bake 2 : t = ***40*** *min*

Exposure : E = **250** [mJ/cm^2] I =

 ≈ ***11*** *s*

Post Bake :

|  |  |  |
| --- | --- | --- |
| ***65****°C* | *ramp* | ***95****°C* |
| ***1*** *min* | ***5*** *min* |

Develop : t = ***20*** *min* Hard Baking : about ***25*** *min* @ ***200°***C